

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	113947	semiconductor wafer	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:08
S2	2064806	defect or feature	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:01
S3	123259	diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:01
S4	1277	machine learning	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:02
S5	77	machine-learning	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:02
S6	1277	S4 or S5	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:40
S7	33553	S1 and S2	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:40
S8	2856	S1 and S3	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:40
S9	12	S1 and S6	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:40
S10	2128	S7 and S8	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 10:41
S11	5	S10 and S4	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 11:14
S12	407	scatterometry	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 11:15

S13	5	S12 and S6	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 11:18
S14	5	S8 and S6	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/22 11:18
S15	0	semiconductor x-ray diffraction metrology system	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:38
S16	0	semiconductor with x-ray diffraction near metrology near system	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:38
S17	0	semiconductor with x-ray near diffraction near metrology near system	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:39
S18	43907	x-ray diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:39
S19	1410217	semiconductor	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:39
S20	6672	metrology	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:39
S21	5753876	system	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:40
S22	31	S19 and S18 and S20 and S21	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:48
S23	2656	wafer near defects	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:49
S24	0	S22 and S23	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:49

S25	0	S18 and S20 and S23	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:49
S26	20	S18 and S23	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:50
S27	99	S20 and S23	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 16:50
S28	93	S27 and S21	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 17:07
S29	123259	diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 17:07
S30	142	S29 and S19 and S23	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 17:08
S31	17	S30 and S20	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/23 17:08
S32	0	simulation of light diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:08
S33	0	simulation of diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:08
S34	9835	computer simulation	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:09
S35	106027	simulation	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:09
S36	3899	light diffraction	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:09

S37	166	S35 and S36	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:11
S38	21415	neural (network or net) or machine learning	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:12
S39	7	S37 and S38	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/09/26 13:12

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	202	(706/12).CCLS.	USPAT; USOCR	OR	OFF	2005/09/28 10:30